

High-k Gate Dielectrics for ScAlN Barrier HEMT Structures

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Supplemental

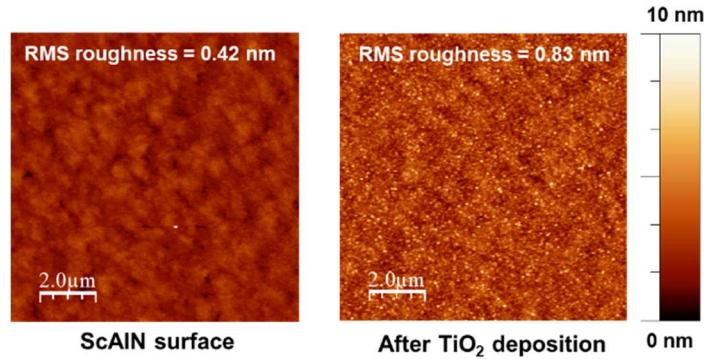


Fig. 1 AFM images of ScAlN surface of ScAlN HEMT structure before and after TiO₂ deposition.

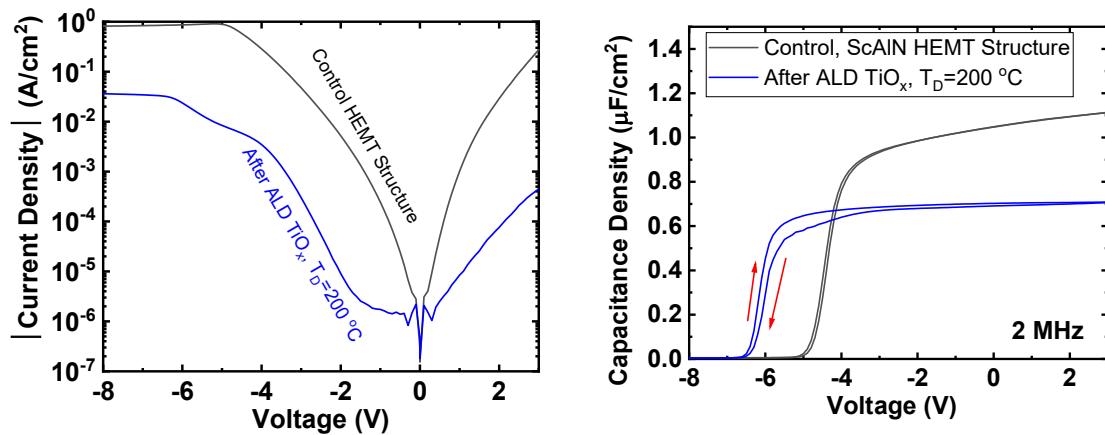


Fig. 2 Vertical I-V and C-V of ScAlN HEMT structure with Schottky contact (black line) compared to structure with ALD TiO₂ (blue line).